Code No.: 13452 S N/O

VASAVI COLLEGE OF ENGINEERING (AUTONOMOUS), HYDERABAD

Accredited by NAAC with A++ Grade

B.E. (E.C.E.) III-Semester Supplementary Examinations, August-2023 Electronic Devices

Time: 3 hours

Max. Marks: 60

Note: Answer all questions from Part-A and any FIVE from Part-B

Part-A $(10 \times 2 = 20 \text{ Marks})$

The second second	Stem of the question	M	L	CO	PC
1.	For a particular semiconductor material, N _C = 1.5 x 10 ¹⁸ cm ⁻³ ,	2	3	1	1
	N_V = 1.3 x 10 ¹⁹ cm ⁻³ and E_G =1.43 eV at T=300Kelvin.Determine the position of the intrinsic Fermi level with respect to the center of the band gap. Assume n_i = 1.5×10 ¹⁰ cm ⁻³				
2.	Is it true that a P-type silicon sample has a higher conductivity compared to an N-type silicon sample having the same doping concentration? Justify your answer.	2	3	1	1
3.	Draw piecewise linear model for Ideal diode and practical diode.	2	1	4	1
4.	Characteristics of PN-Junction Diode depends on Temperature changes. Justify the statement.	1	2	2	1
5.	For the given circuit the potential of the battery is varied from 10V to 16V. If by Zener diode breakdown voltage is 6V, find maximum current through Zener diode.	2	3	3	1
	★ 4kΩ				
	0				
6.	Distinguish Schottky Barrier Diode and normal FN Junction Diode	2	2	2	1
6.		2 2	2	2 5	1
	Distinguish Schottky Barrier Diode and normal FN Junction Diode The transistor has I E = 10mA and α dc = 0.98. Determine the values	2	3		
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7.8.9.	Distinguish Schottky Barrier Diode and normal FN Junction Diode The transistor has I $_{\rm E}$ =10mA and α $_{\rm dc}$ =0.98. Determine the values of I $_{\rm C}$ and I $_{\rm B}$. Distinguish Bipolar and MOS technologies with respect to package density and power dissipation. What is twin tub process in CMOS fabrication?	2 2 2	321	556	1 1,7
7.8.9.	Distinguish Schottky Barrier Diode and normal FN Junction Diode The transistor has I $_{\rm E}$ =10mA and α $_{\rm dc}$ =0.98. Determine the values of I $_{\rm C}$ and I $_{\rm B}$. Distinguish Bipolar and MOS technologies with respect to package density and power dissipation. What is twin tub process in CMOS fabrication? List the advantages of CMOS invertor over other invertor circuits Part-B (5 × 8 = 40 Marks)	2 2 2	321	556	1 1,7

12. a) Show that the diode current equation is $I = I_0[e^{(V/\eta VT)} - 1]$ when the diode is forward biased	4	3	2	1
- Line aborectoristics of PN Junction and Explain.	4	2	2	1
b) Draw the switching characteristics of Treesaward applications of State Clamping theorem and write any two applications of clampers.	4	1	3	1
b) Draw the characteristics of Tunnel Diode and explain them with the help of Energy band diagram.	4	3	3	1
Explain the operation of BJT in CB configuration with the help of its input and output characteristics.	4	1	5	1
- 1 : the C V characteristics of MOS Structure.	4	2	5	1
CMOS invertor with capacitor as load.	4	2	5	1
b) Discuss the process of ion implantation & Etching used in fabrication of Electronic Devices.	4	1	6	1,7
Discuss the concept of Carrier generation and recombination that takes place in semiconductors and its affect on current density.	4	2	1	1
b) Show that depletion capacitance of a step PN junction is	4	3	2	1
$C = \left \frac{dQ}{dV} \right = \frac{\varepsilon_0 A}{d}$				
17. Answer any <i>two</i> of the following:				
a) Assume the diodes to be ideal and find the values of I and V	4	3	3	1,2
+9V +5V				
10 kΩ \$ 10 kΩ				
10 κΩ \$ 10 κΩ				
The CD CE and CC configurations of BIT		4	3	5
b) Distinguish CB, CE and CC configurations of BJTc) List the steps in MOS fabrication process and explain them briefly	y.	4	2	6 1
c) List the steps in MOS labilication process and one PO:	Prog	ramr	ne Out	come

M: Marks; L: Bloom's Taxonomy Level; CO; Course Outcome; PO: Programme Outcome

		20%
;)	Blooms Taxonomy Level – 1	2070
1)	Towns I avol 2	40%
ii)	Blooms Taxonomy Level – 2	
	Blooms Taxonomy Level – 3 & 4	40%
iii)	Blooms Taxonomy Dever 3 co	